ABSTRACT

Method and device for controlling the manufacture of semiconductor by measuring contamination

An object of the present invention is a device for handling substrates within a semiconductor manufacturing plant having substrate processing equipments, substrate storage means, substrate transport means, and a manufacturing execution system (MES) functionally related with the substrate processing equipments, with the substrate storage means and with the substrate transport means, comprising:
- at least one substrate storage and transport box that is transported by the transport means and stored in the storage means,
- at least one gas analysis device of the gases forming the internal atmosphere of the substrate storage and transport box, which produces analysis signals representative of the quantity of the critical gas that is likely to generate molecular contamination, which is present in the storage and transport box,
- an execution device which pilots the transport means and the storage means, with the execution device comprising instructions for detecting a molecular decontamination need as a function of analysis signals emitted by the gas analysis device.

Figure to publish: Fig. 1